

Docket Number: 081468-0306525
Client Reference: P-1586.010-US

IP
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

LOF et al.

Group Art Unit: 2882

Application No.: 10/705,816

Examiner: Unassigned

Filed: November 12, 2003

Confirmation No.: 5408

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

January 7, 2005

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

| Examiner's Initials | First Inventor | Application No. | Filing Date | Enclosed |
|---------------------|--|-----------------|-------------|---|
| | SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1) | 10/367,910 | 02/19/2003 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input type="checkbox"/> Other: stamped receipt card |
| | HOOGENDAM et al. (081468-0308674) | 10/831,370 | 04/26/2004 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |

*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

PLEASE DO NOT PRINT the above information on the patent which results from this application.

Consideration of each listed application is earnestly solicited since unpublished patent applications are contemplated as IDS material; see the exception in Rule 98(a)(2)(iii) and note the penultimate sentence of MPEP 609.

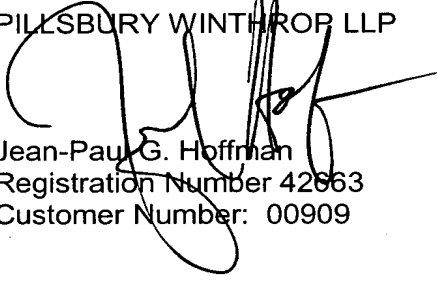
Further, in keeping with MPEP 609, subsec. C(2), 2nd para., line 10 to end of the paragraph (especially note lines 18-25) **PLEASE RETURN A COPY OF THIS LETTER** with the Examiner's initials adjacent each above listing so that applicant will know that each listed application has been considered as required by PTO policy.

Secondly, please consider each document which is listed on the attached Form PTO-1449 and return a copy of that form with the Examiner's initials adjacent each citation, a copy of each document enclosed except for any U.S. patents and published patent applications. It is respectfully requested that these documents listed on the Form PTO-1449 be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

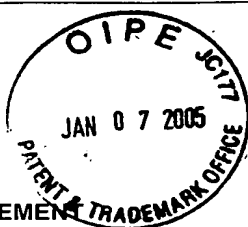
Respectfully Submitted,

PILLSBURY WINTHROP LLP



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|-------------------|--------|---------------|
| Atty. Dkt. No. | M# | Client Ref. |
| | 306525 | P-1586.010-US |

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

| | |
|-----------------|-------------------|
| Applicant: | LOF et al. |
| Appln. No. | 10/705,816 |
| Filing Date: | November 12, 2003 |
| Examiner: | Unknown |
| Group Art Unit: | 2882 |

Date: January 7, 2005 Page 1 of 2

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| Examiner's Initials* | | Document Number | Date MM/YYYY | Name (Family Name of First Inventor) | Class | Sub Class | Filing Date (if appropriate) |
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Examiner: _____ Date Considered: _____

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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|---|-------------------|--------------------------------|----------------------------------|
| FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office | Atty. Dkt. No. | M# 306525 | Client Ref. P-1586.010-US |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | | Applicant: LOF et al. | |
| | | Appln. No. 10/705,816 | |
| | | Filing Date: November 12, 2003 | |
| | | Examiner: Unknown | Group Art Unit: 2882 |
| Date: January 7, 2005 Page 2 of 2 | | | |

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| Examiner's Initials* | | Document Number | Date MM/YYYY | Name (Family Name of First Inventor) | Class | Sub Class | Filing Date (if appropriate) |
| | AR | | | | | | |
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| *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant. | |